



AF # 2823 (In)

**PATENT**  
**Attorney Docket No. TI-25250**  
**Application No.: 09/199,829**  
**Customer No.: 23494**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

**In re Application of:**

SMITH et al.

**Application No.: 09/199,829**

**Filed: November 25, 1998**

**For: HYDROGEN PLASMA  
PHOTORESIST STRIP AND  
POLYMERIC RESIDUE  
CLEANUP PROCESS FOR  
OXYGEN-SENSATIVE  
MATERIALS**

**Group Art Unit: 2823**

**Examiner: Julio J. MALDONADO**

## MAIL STOP AMENDMENT

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

## REQUEST FOR RECONSIDERATION

**Sir:**

In reply to the Final Office Action dated June 14, 2005, the period for reply having been extended for one month by a request for extension and fee payment filed concurrently herewith, please accept this Request for Reconsideration of the application:

**Remarks** begin on page 2 of this paper.